# The influence of channel length to the characteristics of CuPc based OFET thin films

by Fianti Fianti

**Submission date:** 14-Jul-2019 11:08PM (UTC+0700)

**Submission ID:** 1151701967

File name: Sujarwata 2018 J. Phys. 3A Conf. Ser. 983 012016.pdf (493.38K)

Word count: 1755 Character count: 8906

### PAPER · OPEN ACCESS

# The Influence of channel length to the characteristics of CuPc based OFET thin films

To cite this article: Sujarwata et al 2018 J. Phys.: Conf. Ser. 983 012016

View the <u>article online</u> for updates and enhancements.

### Related content

- Application of calendering for improving the electrical characteristics of a printed top-gate, bottom-contact organic thin film transistors Sang Hoon Lee, Dong Geun Lee,

Sang Hoon Lee, Dong Geun Lee, Hoeryong Jung et al.

- <u>Copper phthalocyanine organic thin-film transistors</u>
Shunyang Yu, Mingdong Yi and Dongge

 Improvement of properties of an ambipolar organic field-effect transistor by using a singlet biradicaloid film Wataru Yamane, Harunobu Koike, Masayuki Chikamatsu et al.

doi:10.1088/1742-6596/983/1/012016

# The influence of channel length to the characteristics of CuPc based OFET thin films

### Sujarwata<sup>1,\*</sup>, L Handayani<sup>1</sup>, Mosik<sup>1</sup> and Fianti<sup>1</sup>

<sup>1</sup>Physics Department, Faculty of Mathematics and Natural Sciences, Universitas Negeri Semarang, Indonesia

\*Corresponding author: sjarwot@yahoo.co.id

Abstract. The main focus of this research is to characterize organic field effect transistor (OFET) thin films based on CuPc with a *bottom-contact* structure and varied *channel length*. OFET was prepared by Si substrate cleaning in the ultrasonic cleaner first, then deposition of the *source* and *drain* electrodes on the substrate with vacuum evaporation at room temperature, and finally CuPc thin film deposition among the *source*, *drain*, and *gate* electrodes. The distance between *source* and *drain* electrodes is the *channel length* of the CuPc thin film. In this research, the *channel length* was varied;  $100 \ \mu m$ ,  $200 \ \mu m$  and  $300 \ \mu m$ , with the same active areas of 2.9-3.42 V and different current,  $I_{DS}$ . The result showed that the shorter *channel length* causes, the bigger  $I_{DS}$  flowing on the OFET

### 1. Introduction

Phthalocyanine as semiconductor materials and its derivatives have potential commercial aspects and offer better applications than that of silicon [1]. This material also exhibits high sensitivity to the gas acceptor (like electrons) and high absorption on the crystal surface of thin films followed by the charge transfer reaction affecting the electrical carrier concentration which increases the conductivity. Based on research in 1995, phthalocyanine is a complex compound suitable for gas sensor equipment and detecting NO2 gas [2]. The organic field effect transistor (OFET) principles are: applied gate voltage generating the electric field by the accumulation of charge carriers at the interface between the dielectric gate and the organic materials, as channel materials [3]. The charge carriers (hole/electron) is different in the applied gate voltage. The number of the free charge carriers at the channel depends on the gate voltage, and it can be varied. Therefore, the number of charge carriers between the semiconductor and the gate will increase when the gate voltage is higher. When the voltage is applied to the drain electrode, the current will flow through the channel, from the source- to the drain electrodes. Thus, the current can be controlled by the applied gate voltage, while the drain voltage is required to manage the charge carriers from the source to the drain [4]. As a new developing sensing platform, organic field-effect transistor (OFET) based sensors have attracted intriguing attention owing to their advantages of plenty organic material resources, mechanical flexibility, and microarray compatibility [5].

This research is due to OFET's advantages compared to silicon-based transistor, an inorganic field effect transistor. OFET is an environmentally friendly material, easy and inexpensive electronics device in fabrication, and simple in its usage, opening an opportunity to be the basis of future microelectronics technologies. The structure of CuPc molecule can be seen in Figure 1. Nowadays, OFET performance has been improved towards the mass a manufacturing. With cheap and great

Content from this work may be used under the terms of the Creative Commons Attribution 3.0 licence. Any further distribution of this work must maintain attribution to the author(s) and the title of the work, journal citation and DOI.

Published under licence by IOP Publishing Ltd

IOP Conf. Series: Journal of Physics: Conf. Series 983 (2018) 012016

doi:10.1088/1742-6596/983/1/012016

potential as future electronic component (for example as a smart card component), thus, this organic material can replace the expensive Si technology [6].

**Figure 1.** The structure of CuPc molecule [7].

In general, a field effect transistor consists of several basic components; conductor, insulator, and semiconductor materials. OFET is a type of transistor with semiconductor material made from an organic material or a polymer. However, when compared with inorganic transistors, OFET charge carrier mobility, in general, is still very low, 1.2 10<sup>-5</sup>cm<sup>2</sup>.V<sup>-1</sup>.s<sup>-1</sup> [8]. Phthalocyanine is stable at room temperature and can be deposited as thin films by thermal evaporation [7,9-10]. This material can also be applied for photoconductive and photovoltaic, which its current response has been reviewed [3,11-12].

CuPc material is a fascinating topic to be studied further because it has high sensitivity to existing gas. In this research, the CuPc thin film was grown on the substrate Si/SiO<sub>2</sub> by vacuum evaporation at room temperature. The growth of CuPc thin films was used as the basis for OFET formation.

### 2. Methods

### 2.1. OFET preparation

OFET thin films were prepared by forming *bottom-contact* structure, Figure 2. First, Si substrate was cleaned, with ethanol in the ultrasonic cleaner,then *source-* and *drain-*film were deposited on the substrate by pure gold. This deposition was done by lithography techniques and vacuum evaporation at room temperature. Each method differs in complexity, the number of sensors used the cost and effectiveness [13]. Finally, CuPc thin film was deposited between and on *source* and *drain*, Figure 2.

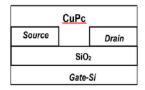


Figure 2. OFET with bottom-contact structure.

### 2.2. OFET characterization

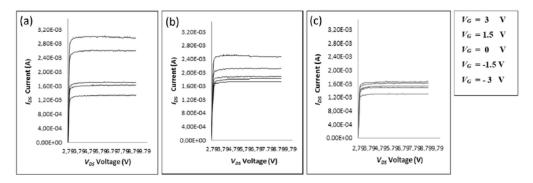
OFET characterization is performed to determine the resistance, conductivity, and mobility of the carrier. I-V characterization was done by connecting the source to the grounded, while the *gate*- and drain electrodes were connected, reverse bias. To measure the mobility, the current flowing from the *source* to the *drain* which the current (I<sub>DS</sub>) was measured by varying the drain voltage (V<sub>D</sub>) for each value of the gate voltage (V<sub>G</sub>). Therefore it can be said that the observation of the situation is due to the saturation of I<sub>DS</sub> pinch-off of channel [3].

IOP Conf. Series: Journal of Physics: Conf. Series 983 (2018) 012016

doi:10.1088/1742-6596/983/1/012016

### 3. Result and Discussion

OFET characterization can be seen in Figure 3. The *gate* potential is varied; -3, -1.5, 0, 1.5, and 3 V, while the applied voltage between source and *drain* is 3 V.



**Figure 3**. I-V characteristic of the semiconductor with (a) 300 μm, (b) 200 μm, and 100 μm *channel length* 

The results in Figure 3 shows that the  $V_{DS}$  increasing causes  $I_{DS}$  increasing until the saturation point of the transistor, as described in Ohm's law. If  $V_{DS}$  increased, depletion area continues to rise, so that eventually occurs in conditions of a *cut-off* voltage  $(V_P)$ . While the value of the voltage  $V_{DS}$  that causes *cut off* and called the cut-off failure despite an increase in the value of  $V_{DS}$  increases. Drain current  $I_{DS}$  OFET at that time is the maximum drain current  $(I_{DS})$  and is achieved when  $V_G = 0$  V and  $V_{DS} > |V_P|$ . For the analysis of the active area OFET, just to the *gate* voltage  $V_G = 0$  volts, as shown in Figure 3.

I-V characteristics of OFET with a channel length 100 μm isain the active area  $V_D$  of 2.79 V to 3.42 V and current  $I_D$  1.95x10<sup>-4</sup> A to 16.9x10<sup>-4</sup> A. As for the saturation area OFET at a voltage  $V_D$  of 3.43-9 V, and this is a *cut-off* area.I-V characteristics of OFET with a channel length 200 μm a shows an active area,  $V_{DS}$ , in 2.79-3.42 V and current  $I_{DS}$  1.49 10<sup>-4</sup> A to 1.49 10<sup>-3</sup> A. While the saturation area OFET at a voltage  $V_{DS}$  of 3.43 V to 9 V and this is a *cut-off* area. I-V characteristics of OFET with a channel length 300 μmshows the active area,  $V_D$ , 2.79-3.43 V and strong current  $I_{DS}$  5.77x10<sup>-6</sup> A to 1.3x10<sup>-3</sup>A. As for the OFET saturation area at a voltage,  $V_{DS}$  of 3.43 V to 9 V and this is a *cut-off* area.

### 4. Conclusion

OFET CuPc based thin films have successfully been prepared with a channel lengtha  $100\mu m$ ,  $200~\mu m$ , and  $300~\mu m$ . They have the same active area of 2.79~V to 3.4~V. The size of CuPc OFET is small  $6.15~mm^2$  that make it easy to *mobile*. The length of a channel on OFET causes the smaller OFET current on the a*gate* voltage of 0~V.

### References

- [1] Sujarwata, Kusminarto and Triyana K 2015 Chemistry and Materials Research 7 119
- [2] Mirwa A, Friedrich M and Hofman A 1995 Sensors and Actuator B, 24-25 596
- [3] Ozer LM, Ozer M, Altindal A, Ozkaya AR, Salih B and Ozer B 2013 Dalton Trans. 42 6633
- [4] Jung BJ, Tremblay NJ, Yeh ML and Katz HE 2011 Chem. Mater. 23 568
- [5] Han S, Zhuang X, Shi W, Yang X, Li L and Yu J 2016 Sens. Actuators B Chem. 225 10
- [6] Rost H, Ficker J, Alonso JS, Leenders L and Culloch IMc 2004 Synthetic Metals 145 83
- [7] Puigdollers J, Voz C, Fonrodona M, Cheylan S, Stella M, Andreu J, Vetter M and Alcubilla R 2006 Journal of Non-Crystalline Solids 352 1778
- [8] Lee HS, Cheon MW and Park YP 2011 Transactions on Electrical and Electronic Materials 12

IOP Conf. Series: Journal of Physics: Conf. Series 983 (2018) 012016

doi:10.1088/1742-6596/983/1/012016

- [9] Maggioni G, Carturan S, Tonezzer M, Quaranta A and Della Mea G 2008 Sensors and Actuators B 131 496
- [10] Warner M, Din S, Tupitsyn IS, Morley GW, Stoneham AM, Gardener JA, Wu Z, Fisher AJ, Heutz S, Kay CWM and Aeppli G 2013 Nature 503 504
- [11] Korodi IG, Lehmann D, Tippo T, Hietschold M and Zahn DRT 2010 Phys. Status Solidi C 7 456
- [12] Karimov KS, Qazi I, Tahir MM, Khan TA and Shafique U, 2008 Turk J. Phys. 32 13
- [13] Alik R, Jusoh A and Sutikno T 2015 TELKOMNIKA 13 745

## The influence of channel length to the characteristics of CuPc based OFET thin films

**ORIGINALITY REPORT** 

SIMILARITY INDEX

INTERNET SOURCES

**PUBLICATIONS** 

STUDENT PAPERS

MATCH ALL SOURCES (ONLY SELECTED SOURCE PRINTED)

3%

★ Sang Hoon Lee, Hwiwon Seo, Sangyoon Lee. "Fabrication of a printed capacitive air-gap touch sensor", Japanese Journal of Applied Physics, 2018 Publication

Exclude quotes

Off

Exclude matches

< 4 words

Exclude bibliography

Off